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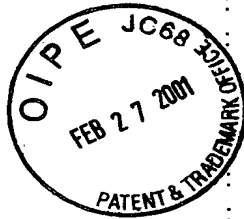
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Satoshi Watanabe et al.

Serial No.: 09/401,490

Filed: September 22, 1999



Group Art Unit: 1765

Examiner: V. Perez-Ramos

For: RESIST COMPOSITION AND PATTERNING METHOD

RESPONSE TO RESTRICTION REQUIREMENT

Assistant Commissioner of Patents
Washington, DC 20231

Sir:

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Claims in the above-identified application are 1-8. Applicant(s) hereby elect with traverse Group I, claims 1-3 drawn to a resist composition. Applicants traverse the Restriction Requirement on the basis that the Examiner has not established that examining all of the claims in the application would not constitute a serious burden (See MPEP §803).

Respectfully submitted,


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Filed: February 27, 2001

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